

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L6	1	(electrode and gate and (SiN or SiO or nitride) and etch\$4 and "hard mask" and spacer and stack\$3 and "landing plug" and contact and planariz\$3 and conduct\$3).clm.	US-PGPUB	OR	ON	2005/11/17 16:24
L7	4	chung-su-ock.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 16:24